

11002 U.S. PTO  
10/08/2010  
02/22/02

PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10082010	02/22/2002	438	79	2813	Vela

\*\*APPLICANTS: Singh Rajiv; Lee Seung-Mahn;

\*\*CONTINUING DATA VERIFIED:

\*\* FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiner's initials		<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no
ATTORNEY DOCKET NO 5853-224		
TITLE : Slurry and method for chemical mechanical polishing of metal structures including refractory metal based barrier layers		
U.S. DEPT. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)		

BEST AVAILABLE COPY

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED		
Assistant Examiner		Total Claims      Print Claim for O.G.		
Primary Examiner		DRAWING		
PREPARED FOR ISSUE		Sheets Drwg.      Figa.Drwg.      Print Fig.		
TERMINAL DISCLAIMER		Application Examiner		
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.				

FILED WITH:

DISK (CRF)

CD-ROM

(Attached in pocket on right inside flap)